



## Correction: Modelling focused electron beam induced deposition beyond Langmuir adsorption

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### Correction

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The originally published Equation 1 contains a mistake. The theta factor in the second right term is missing. The correct Equation 1 is

$$\frac{\partial \theta}{\partial t} = \frac{sF}{N_0} (1 - \theta) - \nu_0 e^{\frac{-E}{k_B T}} \theta - \sigma J \theta. \quad (1)$$

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